

<b>FORM PTO-1449</b>	<b>Docket No.:</b> 2004P51130US/1331.128.101	<b>Serial No.:</b> 10/816, 503
<b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b>	<b>Applicant:</b> Hong-Jyh Li	
	<b>Filing Date:</b> Herewith	<b>Group Art:</b> 2887

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate
98	AA 6,660,660	12/09/2003	Haukka et al.			
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
	AL					

**FOREIGN PATENT DOCUMENTS**

	Document No.	Date	Country	Class	Sub Class	Translated Yes No
	AM					Yes
	AN					Yes

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

9	AP	Yankov, Rossen A. and Mändl, Stephan, "Plasma Immersion Ion Implantation for Silicon Processing", Ann. Phys. (Leipzig) 10 4, pp. 279-298, (2001).
9	AQ	Ensinger, W., "Semiconductor Processing by Plasma Immersion Ion Implantation", Materials Science and Engineering, pp. 258-268, (1998).

<b>EXAMINER:</b> <i>Phillip J. Hunt</i>	<b>DATE CONSIDERED:</b> 9-15-05
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.